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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/803,083		Thomas P. Glenn	G0049M	
75	690 04/20/2004		EXAM	INER
Serge J. Hodgson			MALDONADO, JULIO J	
Gunnison, McK	ay & Hodgson, L.L.P			
1900 Garden Road, Suite 220			ART UNIT	PAPER NUMBER
Monterey, CA 93940			2823	

DATE MAILED: 04/20/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
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Office Action Summary	09/803,083	GLENN ET AL.			
omec Action Cummary	Examiner	Art Unit			
The MAILING DATE of this communication app	Julio J. Maldonado	2823			
Period for Reply	surs on the cover sheet with the c	on espondence dadress			
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a reply - If NO period for reply secified above, the maximum statutory period wi - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	6(a). In no event, however, may a reply be tim within the statutory minimum of thirty (30) days ill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONEI	rely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).			
Status					
Responsive to communication(s) filed on 29 December 2a)    This action is <b>FINAL</b> .    2b)    This 3)    Since this application is in condition for allowan closed in accordance with the practice under Expression	action is non-final. ce except for formal matters, pro				
Disposition of Claims					
4)  Claim(s) 1 and 3-21 is/are pending in the application 4a) Of the above claim(s) is/are withdraw 5)  Claim(s) 3 and 14-21 is/are allowed.  6)  Claim(s) 1 and 4-13 is/are rejected.  7)  Claim(s) is/are objected to.  8)  Claim(s) are subject to restriction and/or	n from consideration.				
Application Papers					
9)☐ The specification is objected to by the Examiner					
10)☐ The drawing(s) filed on is/are: a)☐ acce	pted or b) $\square$ objected to by the E	xaminer.			
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).					
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).					
11)☐ The oath or declaration is objected to by the Exa	aminer. Note the attached Office	Action or form PTO-152.			
Priority under 35 U.S.C. § 119					
12) Acknowledgment is made of a claim for foreign   a) All b) Some * c) None of:  1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priori application from the International Bureau * See the attached detailed Office action for a list of	have been received. have been received in Application ty documents have been receive (PCT Rule 17.2(a)).	on No d in this National Stage			
Attachment(s)  1) Notice of References Cited (PTO-892)  2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	4)				
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 2003/08/27.		atent Application (PTO-152)			

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#### **DETAILED ACTION**

## Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1, 4-7 and 9-13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Wojnarowski (U.S. 5,888,884) in view of Roberts, Jr. et al. (U.S. 5,362,681).

Wojnarowsky (Figs.1-7 and 9) teaches a method to form alignment marks (90) comprising coupling a wafer support to a first surface of a substrate; aligning a drilling device at a first intersection of a first scribe line and a second scribe line coupled to a first surface (32) of a substrate (30); drilling through said substrate (30) at said first intersection with said drilling device from said first surface (32) of said device from said first surface to a second surface (34) of said substrate to form an alignment mark (90); aligning a saw (400) with said first scribe line using said alignment mark (90), wherein said saw (400) comprises a laser saw and cutting said substrate (30) comprises cutting on the scribe lines from said second surface (34) (see Fig.7); and singulate electronic components (36) of said substrate (30), wherein said electronic components comprises integrated circuits (column 6, line 20 – column 8, line 65).

Wojnarowsky fail to teach coupling a front-side surface of a wafer to an interior surface of a transparent wafer support; optically recognizing a scribe grid coupled to

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said front-side surface of said wafer, wherein said support protects the front surface of said substrate; and washing said substrate to remove contaminants generated during said cutting. However, Roberts Jr., et al. (Figs.2-5) in a related method to singularize a semiconductor wafer teach coupling a front-side surface of a wafer (32) to an interior surface of a transparent wafer support (26), wherein said support protects the front surface of said substrate and is sufficiently transparent to allow intersections in a wafer to be optically inspected through said wafer support (26); and washing said substrate to remove contaminants generated during said cutting (column 7, line 33 – column 9, line 7). Therefore, it would have been obvious to one of ordinary skill in the art to combine the teachings of Roberts Jr. et al. and Wojnarowsky to enable the steps of coupling a front-side surface of a wafer to an interior surface of a wafer support, and furthermore because this would result in a method of separating individual dies that will provide better protection to the microstructures formed in said die (column, 3, lines 37 – 61).

3. Claim 8 is rejected under 35 U.S.C. 103(a) as being unpatentable over Wojnarowski ('884) in view of Roberts, Jr. et al. ('681) as applied to claims 1, 4-7 and 9-13 above, and further in view of Summerer (U.S. 6,537,836 B2).

The combined teachings of Wojnarowski and Roberts, Jr. et al. substantially teach all aspects of the invention but fail to show shining light of an angle to said second surface of said substrate to enhance recognition of said alignment mark. However, Summerer (Fig.1) in a related method for alignment of substrates teaches shining light of an angle to a surface of a substrate (12) to detect alignment marks (column 2, lines 4 – 31). Therefore, it would have been obvious to one of ordinary skill in the art at the

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Summerer to enhance recognition of an alignment mark in a second surface of a substrate in Wojnarowsky and Roberts, Jr. et al., since illuminating methods are well-known in the art to properly align a semiconductor substrate (column 1, lines 11 - 28).

## Allowable Subject Matter

- 4. Claims 3 and 14-21 are allowed.
- 5. The following is a statement of reasons for the indication of allowable subject matter:

The prior art of record, Wojnarowski to U.S. 5,888,884 teaches a method to form alignment marks (90) comprising aligning a drilling device at a first intersection of a first scribe line and a second scribe line coupled to a first surface (32) of a substrate (30); drilling through said substrate (30) at said first intersection with said drilling device from said first surface (32) of said device from said first surface to a second surface (34) of said substrate to form an alignment mark (90); aligning a saw (400) with said first scribe line using said alignment mark (90), wherein said saw (400) comprises a laser saw and cutting said substrate (30) comprises cutting on the scribe lines from said second surface (34) (see Fig.7); and singulate electronic components (36) of said substrate (30), wherein said electronic components comprises integrated circuits (see Figs.1-7 and 9 and column 6, line 20 – column 8, line 65).

However, Wojnarowski fails to teach optically recognizing said first intersection through said wafer support.

## Response to Arguments

6.— Applicant's arguments filed 12/29/2003 have been fully-considered but they are not persuasive.

Applicants argue, "...As discussed further below, Wojnarowski teaches that the front-side surface of the wafer must be processed after formation of the 'alignment holes'. Accordingly, one of skill in the art would have no motivation to apply the 'wafer support' of Roberts Jr., et al. to this front-side surface prior to the formation of the 'alignment holes' since this would defeat the ability to process the front-side surface. For at least this reason, Applicants submit that amended Claim 1 is allowable over Wojnarowski in view of Roberts Jr., et al...". This is not persuasive because it's inherent in Wojnarowski to place a support on the wafer prior to form the alignment marks. And according to Roberts Jr., et al., the use of a transparent support using a transparent support provides better protection to the microstructures formed in said die (column, 3, lines 37 – 61).

Also, in response to applicants' arguments that the combination of Wojnarowski and Roberts Jr., et al. would be inoperative because Wojnarowski further teaches processing the surfaces of the wafer, the rejected claims are open to encompass the process disclosed in Wojnarowski after using the support of Roberts Jr.

#### Conclusion

7. **THIS ACTION IS MADE FINAL.** Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

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A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

- 8. Any inquiry of a general nature or relating to the status of this application should be directed to the Group Receptionist whose telephone number is 571-272-2800. See MPEP 203.08.
- 9. Any inquiry concerning this communication or earlier communications from the examiner should be directed to examiner Julio J. Maldonado whose telephone number is (571) 272-1864. The examiner can normally be reached on Monday through Friday.
- 10. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri, can be reached on (571) 272-1855. The fax number for this group is 703-872-9306 for before final submissions, 703-872-9306 for after final submissions and the customer service number for group 2800 is (703) 306-3329. Updates can be found at http://www.uspto.gov/web/info/2800.htm.

Julio J. Maldonado Patent Examiner Art Unit 2823

George Fourson
Primary Examiner

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